

AMENDMENTS TO THE SPECIFICATION

Page 1, paragraph 3 (bridging pages 1 and 2) has been amended to read:

There are various manners applicable to the development. It is common in the art to have the liquid developer sprayed onto the surface of a substrate mounted on a rotating device. As shown in FIG. 2, a developing apparatus 100 is equipped with a rotating device 110 having an outer cup 120 at the outer periphery of the rotating device 110. A guard means 121 having a length of about 10 cm is integrally formed with the outer cup 120, being made of stainless steel to form a smooth surface. The guard means 121 is mounted at the upper periphery of the outer cup 120. With this arrangement, the liquid developer is prevented from splashing outwardly, as indicated by arrow 130, to the ambient area of the development apparatus when the rotating device 100 is in high speed rotation. However, some of the liquid developer splashes back to the substrate, as indicated by an arrow 131 in FIG. 2, because the liquid developer hits against the stainless steel guard means 121 at high speed. The splashed-back developer brings about an adverse effect on yield of production, and tends to be worse as far as a thinner substrate is concerned. If a thinner substrate is provide din high speed rotation, the peripheral portion of the substrate will be lifted up higher and more of the splashed-back developer will be present, as indicated by an arrow 132 in FIG. 2. For example, the amount of the splashed-back liquid developer occurring in a glass substrate having a thickness of 0.63 mm is more than that occurring in a glass substrate having a thickness of 0.7 mm.

Page 6, paragraph 1 has been amended to read:

It is certain that the roughness of the surface of the guard means 40 is increased by adding the stainless steel web 50 at an upper periphery of the guard means 40 to reduce an elastic impact caused by the liquid molecules on the surface of the guard means 40. In addition to the stainless steel web 50 as used in the present embodiment, any other material capable of increasing the roughness of the surface of the guard means 40 can be

adopted for achieving the same or similar purpose. For instance, a sponge may be used, or alternatively, the purpose is achieved by directly roughening the surface of the guard means 40. Hence, the elastic compact caused by the liquid molecules of the developer by hitting against the surface of the guard means is greatly reduced so as to prevent the developer from splashing back to the substrate surface. Moreover, the method for roughening the surface of the guard means 40 can be compelled by mechanical knock, blast, surface spray, friction or chemical etch, etc. Furthermore, the present invention can also be applied to any processing apparatus having a liquid spray mechanism by spin-coating such as the scrubber process.